

Electron beam processing of silicon carbide substrate to obtain graphene-like carbon films

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Nanostructured carbon films: graphene and graphene-like films are considered as future electronics materials for applications in nanoelectronics and carbon electronics [1]. Therefore, achieving their quality synthesis is in demand. Among the various methods of its obtaining the most interesting is the synthesis directly on silicon carbide substrates [2], e.g. thermal decomposition [3, 4]. Recently, various approaches using a irradiation technique or particle beam (laser, ion and electron beams) were extensively paid attention due to high precision, efficiency, mature control method, and fast speed [2, 5, 6]. The application of particle beam irradiation on graphene obtaining could present obvious advantages, including suitability for a large-scale production of graphene.

In this paper, we present our first result on graphene-like films fabrication by electron beam processing of silicon carbide substrate.

Several pieces of 35-42 mm² were cut from a 6H-SiC substrate and chemically cleaned. One sample was served as reference and other samples were then electron beam processed (EBP) for synthesis of graphene. EBP was carried out on a specialized electron beam system based on laboratory vacuum with the Pierce electron gun. An electron current of 50 to 180 mA and beam rate of a few mm/s were applied to heat the samples in pressure of 0.3-0.5 mTorr, so corresponding temperature were in the range of 1680 to 2000 K. The as-received layers as well as initial substrate surfaces on reference sample were characterized by Raman spectroscopy and atomic force microscopy.

A series of {0001} 6H-SiC samples were electron beam processed and nanostructured carbon films were available on the sample surfaces. Raman spectra of some samples are shown in Figure 1.

The D, G and 2D peaks as well as D/G (0.17-0.88) and 2D/G (0.70-0.89) ratios are detected. The FWHM of 2D peaks are 61-81. Temperature effects are discussed.

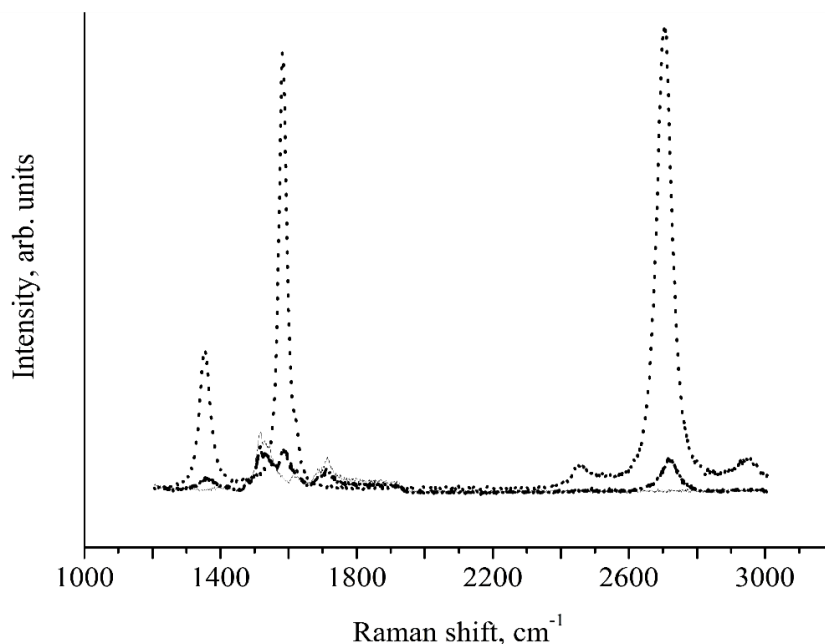


Figure 1. Raman spectra of reference (solid gray line) and electron beam processed (dashed and pointed black lines) 6H-SiC samples.

Comparison of the obtained results with known Raman spectra's and atomic force microscopy data [1-5, 7-9] allows us to assume that nanostructured carbon films, from monolayer to multilayer graphene and turbostratic graphite with various degrees of defects, are formed under the conditions of electron-beam processing.

It is expected that further optimization of the processing conditions will allow to fabricate required nanostructured carbon films.

Different nanostructured carbon films have been synthesized on {0001} 6H-SiC by electron beam processing. The preparation of graphene on silicon carbide substrates by EBP will be promising method in carbon electronic applications.

This study was financially supported by Southern Federal University. The results were obtained using the equipment of the Research and Education Center "Nanotechnologies" of Southern Federal University.

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